

RTP

Zenith-100 RTP - SYSTEM

High temperature RTP system
Annealing processes up to 2000°C
RTP and RTCVD processes
High vacuum



Applications

Silicon Carbide implant annealing

Graphene by SiC sublimation

RTCVD of graphene

High temperature annealing

Specifications

The Zenith-100 high temperature rapid thermal processor can process samples up to 4-inch diameter at temperature up to 2000°C.

The system has a stainless steel water-cooled chamber. The cold wall chamber technology provides significant advantages: low memory effect, higher cooling rates.

The high temperature tungsten heaters provide enhanced temperature uniformity.

The pyrometer associated with the fast digital PID controller assure accurate and repeatable thermal control across the temperature range.

The design process chamber provides easy loading and unloading of the substrates and the installation of the thermocouple for calibration.

Basic features

Substrate size	Up to 100 mm diameter (4-inch)
Process chamber	Stainless steel cold wall chamber technology Low inertia tungsten heating elements
Temperature range	From 450°C up to 2000°C
Temperature control	Pyrometer temperature control Fast digital PID / RTP temperature controller
Vacuum and gas	Up to 8 process gas lines with digital mass flow controllers One purge gas line Vacuum valve and vacuum gauge
Control	Full PC control, up to 100 steps per recipe Human interface designed in respect of SEMI E95-0200 Full data logging and process historicals

Optional features

Graphite and silicon carbide coated susceptors
Rough vacuum pump
Automatic pressure control with throttle valve

Customer support

Outstanding customer support for hardware, software and process
Efficient remote support using software diagnostic capabilities
High expertise in RTP processes of our process engineers
Capability to support customer for process optimization

Physical specifications

	Voltage : 3x400V+N+Gr / 3x220V+Gr
	Power : 38 kW
Facilities	Water : 2 to 4 bars, pressure drop 1 bar, 15 l/mn Compressed air : 6 bars (valve actuation) Process gas fittings : VCR ¼

Dimensions and weight	Width	800 mm	31.5"
	Depth	1,750 mm	68.9"
	Height	2,000 mm	78.8"
	Mass	500 kg	1,102 lbs



Bâtiment T2, PIT de la Pompignane
Rue de la Vieille Poste
34055 Montpellier Cedex 1 - FRANCE

Tel: +33 467 20 23 63
Fax: +33 467 20 26 89
Email : sales@annealsys.com

www.annealsys.com

